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Applicant(s): Yoshinori NISHIWAKI et al.			
Serial No. 10/532,364	Filing Date April 20,2005	Examiner To Be Assigned	Group Art Unit To Be Assigned
Invention: CHEMICALLY AMPLIFIED POSITIVE PHOTSENSITIVE RESIN COMPOSITION			
<div data-bbox="142 457 376 682"></div> <p>I hereby certify that this <u>English Language abstract of JP 62-124556 - 2 Pages</u> (Identify type of correspondence)</p> <p>is being deposited with the United States Postal Service as first class mail in an envelope addressed to: The Commissioner of Patents and Trademarks, Washington, D.C. 20231-0001 on <u>September 21, 2005</u> (Date)</p> <p><u>MARIA T. SANCHEZ</u> (Typed or Printed Name of Person Mailing Correspondence)</p> <p><u></u> (Signature of Person Mailing Correspondence)</p>			
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(54) PHOTSENSITIVE COMPOSITION AND PHOTSENSITIVE LITHOGRAPHIC PLATE MATERIAL

(57)Abstract:

PURPOSE: To obtain a photosensitive composition high in photosensitivity, wide in processing allowance at the time of development, and superior in resistance to processing chemicals by using a novolak type resin containing at least 3 different kinds of phenols only in combination with a positive type photosensitive material composed of a compound capable of generating acid on irradiation of actinic rays and an acid-decomposable type compound.

CONSTITUTION: The photosensitive resin composition contains the compound capable of generating acid on irradiation of actinic rays and a compound having at least one acid-decomposable bond, and the novolak type resin containing at least 3 different kinds of phenols. As the acid-decomposable compound, ones such as having an acetal or ketal group, or polymers each having an orthocarboxylic ester group on the principal chain, are used, preferably, in an amount of 5W70wt% of the total solid of the photosensitive resist-forming composition. As the novolak resin, polycondensed novolak resins containing at least 3 kinds of phenols are preferably used.

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